IN THE CLAIMS:

The following is a complete listing of the claims, and replaces all earlier listings and versions.

1. - 15. (Cancelled)

16. (Currently Amended) A method of manufacturing an electron source comprising steps of:

exposing, of a surface of a substrate to a sealed atmosphere, on which a plurality of electron-emitting devices are to be formed; and

introducing, of a gas containing carbon into the sealed atmosphere, wherein the sealed atmosphere is formed by a chamber and the chamber is heated before said introducing step.

17. (Currently Amended) A method of manufacturing an electron source comprising steps of:

exposing, of a surface of a substrate to a sealed atmosphere, on which a plurality of electron-emitting devices are to be formed; and

introducing, of a gas containing carbon into the sealed atmosphere,

wherein the sealed atmosphere is formed by a chamber and the chamber is heated before said introducing step, to reduce [[a]] moisture absorbed to a surface of the chamber.

18. (Currently Amended) A method of manufacturing an electron source comprising steps of:

exposing; of a surface of a substrate to a sealed atmosphere, wherein an electron-emitting region to be formed is disposed on the surface of the substrate; and introducing, of a gas containing carbon into the sealed atmosphere, wherein the sealed atmosphere is formed by a chamber and the chamber is heated before said introducing step.

- 19. (Currently Amended) The method according to Claim 18, further comprising [[a]] the step of applying a voltage to an electro-conductive member, the electro-conductive member being disposed on the surface of the substrate.
- 20. (Currently Amended) A method of manufacturing an electron source comprising steps of:

exposing, of a surface of a substrate to a sealed atmosphere, wherein an electro-conductive member, in which an electron-emitting region is to be formed, is disposed on the surface of the substrate; and

introducing, of a gas containing carbon into the sealed atmosphere, wherein the sealed atmosphere is formed by a chamber and the chamber is heated before said introducing step, to reduce [[a]] moisture absorbed to a surface of the chamber.

- 21. (Currently Amended) The method according to Claim 20, further comprising [[a]] the step of applying a voltage to the electro-conductive member.
- 22. (Currently Amended) A method of manufacturing an electron source comprising steps of:

exposing, of a surface of a substrate to a sealed atmosphere, wherein an electro-conductive member, capable of being subjected to an activation of an electronemitting function, is disposed on the surface of the substrate; and

introducing, of a gas containing carbon into the sealed atmosphere, wherein the sealed atmosphere is formed by a chamber and the chamber is heated before said introducing step.

23. (Currently Amended) The method according to Claim 22, further comprising [[a]] the step of applying a voltage to the electro-conductive member.

24. (Currently Amended) A method of manufacturing an electron source comprising steps of:

exposing, of a surface of a substrate to a sealed atmosphere, wherein an electro-conductive member, capable of being subjected to an activation of an electron-emitting function, is disposed on the surface of the substrate; and

introducing, of a gas containing carbon into the sealed atmosphere, wherein the sealed atmosphere is formed by a chamber and the chamber is heated before said introducing step, to reduce [[a]] moisture absorbed to a surface of the chamber.

25. (Currently Amended) The method according to Claim 24, further comprising [[a]] the step of applying a voltage to the electro-conductive member.